

L Number	Hits	Search Text	DB	Time stamp
1	53725	plasma near5 process\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:22
2	25007	(plasma near5 process\$3) & chamber\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:23
3	7403	((plasma near5 process\$3) & chamber\$3) & source & current	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:24
4	6177	((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:26
5	2767	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:27
6	408	((((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:27
7	39	((((((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:28
8	19	(((((((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:29
9	8	((((((((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:31
10	0	((((((((((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & antenn\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:32
11	8	(((((((((((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:32
12	1	((((((((((((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & (hollow near3 member\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:33

13	8	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:34
14	8	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic) & (process\$3 near3 region)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:35
15	8	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic) & (process\$3 near3 region)) & gas\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:36
16	8	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic) & (process\$3 near3 region)) & gas\$3) & (clean\$3 etch combinat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:37
17	8	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic) & (process\$3 near3 region)) & gas\$3) & (clean\$3 etch combinat\$4)) & generat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:38
18	8	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic) & (process\$3 near3 region)) & gas\$3) & (clean\$3 etch combinat\$4)) & generat\$3) & (process\$3 near3 gas\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:40
19	8	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic) & (process\$3 near3 region)) & gas\$3) & (clean\$3 etch combinat\$4)) & generat\$3) & (process\$3 near3 gas\$3)) & (deposit\$3 near3 gas\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:49
20	8	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic) & (process\$3 near3 region)) & gas\$3) & (clean\$3 etch combinat\$4)) & generat\$3) & (process\$3 near3 gas\$3)) & (deposit\$3 near3 gas\$3)) & bias	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:51

21	8	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic) & (process\$3 near3 region)) & gas\$3) & (clean\$3 etch combinat\$4)) & generat\$3) & (process\$3 near3 gas\$3)) & (deposit\$3 near3 gas\$3)) & bias) & adjacent	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:51
22	8	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic) & (process\$3 near3 region)) & gas\$3) & (clean\$3 etch combinat\$4)) & generat\$3) & (process\$3 near3 gas\$3)) & (deposit\$3 near3 gas\$3)) & bias) & adjacent) & (current near3 path)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:52
23	8	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic) & (process\$3 near3 region)) & gas\$3) & (clean\$3 etch combinat\$4)) & generat\$3) & (process\$3 near3 gas\$3)) & (deposit\$3 near3 gas\$3)) & bias) & adjacent) & (current near3 path)) & (magnetic near3 field)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:53
24	2	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic) & (process\$3 near3 region)) & gas\$3) & (clean\$3 etch combinat\$4)) & generat\$3) & (process\$3 near3 gas\$3)) & (deposit\$3 near3 gas\$3)) & bias) & adjacent) & (current near3 path)) & (magnetic near3 field)) & (first near3 portion) & (second near3 portion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:54
25	8	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic) & (process\$3 near3 region)) & gas\$3) & (clean\$3 etch combinat\$4)) & generat\$3) & (process\$3 near3 gas\$3)) & (deposit\$3 near3 gas\$3)) & bias) & adjacent) & (current near3 path)) & (magnetic near3 field)) & portion	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:54
26	8	(((((plasma near5 process\$3) & chamber\$3) & source & current) & first & second) & (coil\$1 induct\$3)) & (plasma near3 source) & (plasma near3 current)) & (plasma near3 hollow\$1)) & (plasma near3 shap\$3)) & showerhead) & rf) & magnetic) & (process\$3 near3 region)) & gas\$3) & (clean\$3 etch combinat\$4)) & generat\$3) & (process\$3 near3 gas\$3)) & (deposit\$3 near3 gas\$3)) & bias) & adjacent) & (current near3 path)) & (magnetic near3 field)) & portion) & chang\$3 & adjust\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/29 16:55

